Ulf Helmersson

List of Publications by Year
in descending order

210 papers	12,408 citations	26610 56 h-index	27389 106 g-index
213 all docs	213 docs citations	213 times ranked	6017 citing authors

#	Article	IF	Citations
1	Dynamics of bipolar HiPIMS discharges by plasma potential probe measurements. Plasma Sources Science and Technology, 2022, 31, 025007.	1.3	10
2	Experimental verification of deposition rate increase, with maintained high ionized flux fraction, by shortening the HiPIMS pulse. Plasma Sources Science and Technology, 2021, 30, 045006.	1.3	18
3	Low temperature growth of stress-free single phase <i>Î±</i>-W films using HiPIMS with synchronized pulsed substrate bias. Journal of Applied Physics, 2021, 129, .	1.1	10
4	Bipolar HiPIMS: The role of capacitive coupling in achieving ion bombardment during growth of dielectric thin films. Surface and Coatings Technology, 2021, 416, 127152.	2.2	16
5	Copper thin films deposited using different ion acceleration strategies in HiPIMS. Surface and Coatings Technology, 2021, 422, 127487.	2.2	16
6	Magnetically Collected Platinum/Nickel Alloy Nanoparticles as Catalysts for Hydrogen Evolution. ACS Applied Nano Materials, 2021, 4, 12957-12965.	2.4	9
7	Tuning the stress in TiN films by regulating the doubly charged ion fraction in a reactive HiPIMS discharge. Journal of Applied Physics, 2020, 127, .	1.1	7
8	Pulse length selection for optimizing the accelerated ion flux fraction of a bipolar HiPIMS discharge. Plasma Sources Science and Technology, 2020, 29, 125013.	1.3	24
9	Roomâ€Temperature Micropillar Growth of Lithiumâ€“Titanateâ€“Carbon Composite Structures by Selfâ€Biased Direct Current Magnetron Sputtering for Lithium Ion Microbatteries. Advanced Functional Materials, 2019, 29, 1904306.	7.8	7
10	Impact of nanoparticle magnetization on the 3D formation of dual-phase Ni/NiO nanoparticle-based nanotrusses. Journal of Nanoparticle Research, 2019, 21, 1.	0.8	5
11	A nanostructured NiO/cubic SiC pâ€“n heterojunction photoanode for enhanced solar water splitting. Journal of Materials Chemistry A, 2019, 7, 4721-4728.	5.2	50
12	Bipolar HiPIMS for tailoring ion energies in thin film deposition. Surface and Coatings Technology, 2019, 359, 433-437.	2.2	70
13	Bipolar high power impulse magnetron sputtering for energetic ion bombardment during TiN thin film growth without the use of a substrate bias. Thin Solid Films, 2019, 688, 137350.	0.8	30
14	Growth of semi-coherent Ni and NiO dual-phase nanoparticles using hollow cathode sputtering. Journal of Nanoparticle Research, 2019, 21, 1.	0.8	9
15	Graphene Decorated with Iron Oxide Nanoparticles for Highly Sensitive Interaction with Volatile Organic Compounds. Sensors, 2019, 19, 918.	2.1	22
16	Plasma-based processes for planar and 3D surface patterning of functional nanoparticles. Journal of Nanoparticle Research, 2019, 21, 1.	0.8	4
17	Catalytic Nanotruss Structures Realized by Magnetic Self-Assembly in Pulsed Plasma. Nano Letters, 2018, 18, 3132-3137.	4.5	16
18	Low-energy ion irradiation in HiPIMS to enable anatase TiO₂ selective growth. Journal Physics D: Applied Physics, 2018, 51, 235301.	1.3	24

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19	Iron Oxide Nanoparticle Decorated Graphene for Ultra-Sensitive Detection of Volatile Organic Compounds. Proceedings (mdpi), 2018, 2, .	0.2	1
20	Low temperature (<i>T</i>s/<i>T</i>mâ€‰<â€‰0.1) epitaxial growth of HfN/MgO(001) via reactive HiPIMS with metal-ion synchronized substrate bias. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, .	0.9	23
21	Nucleation of titanium nanoparticles in an oxygen-starved environment. II: theory. Journal Physics D: Applied Physics, 2018, 51, 455202.	1.3	4
22	Nucleation of titanium nanoparticles in an oxygen-starved environment. I: experiments. Journal Physics D: Applied Physics, 2018, 51, 455201.	1.3	3
23	Phase separation within NiSiN coatings during reactive HiPIMS discharges: A new pathway to grow NixSi nanocrystals composites at low temperature. Applied Surface Science, 2018, 454, 148-156.	3.1	0
24	Performance tuning of gas sensors based on epitaxial graphene on silicon carbide. Materials and Design, 2018, 153, 153-158.	3.3	25
25	Effect of substrate temperature on the deposition of Al-doped ZnO thin films using high power impulse magnetron sputtering. Surface and Coatings Technology, 2018, 347, 245-251.	2.2	25
26	Low-Loss and Tunable Localized Mid-Infrared Plasmons in Nanocrystals of Highly Degenerate InN. Nano Letters, 2018, 18, 5681-5687.	4.5	24
27	Restoring the Properties of Transparent Al-Doped ZnO Thin Film Electrodes Exposed to Ambient Air. Journal of Physical Chemistry C, 2017, 121, 14426-14433.	1.5	10
28	Synthesis of hydrogenated diamondlike carbon thin films using neonâ€"acetylene based high power impulse magnetron sputtering discharges. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2016, 34, 061504.	0.9	18
29	Compressive intrinsic stress originates in the grain boundaries of dense refractory polycrystalline thin films. Journal of Applied Physics, 2016, 119, .	1.1	44
30	The influence of pressure and gas flow on size and morphology of titanium oxide nanoparticles synthesized by hollow cathode sputtering. Journal of Applied Physics, 2016, 120, 044308.	1.1	14
31	Complex 3D nanocoral like structures formed by copper nanoparticle aggregation on nanostructured zinc oxide rods. Materials Letters, 2016, 184, 127-130.	1.3	0
32	Room temperature deposition of homogeneous, highly transparent and conductive Al-doped ZnO films by reactive high power impulse magnetron sputtering. Solar Energy Materials and Solar Cells, 2016, 157, 742-749.	3.0	74
33	Nanoparticle growth by collection of ions: orbital motion limited theory and collision-enhanced collection. Journal Physics D: Applied Physics, 2016, 49, 395208.	1.3	5
34	The role of Ohmic heating in dc magnetron sputtering. Plasma Sources Science and Technology, 2016, 25, 065024.	1.3	41
35	Modified Epitaxial Graphene on SiC for Extremely Sensitive and Selective Gas Sensors. Materials Science Forum, 2016, 858, 1145-1148.	0.3	8
36	Process stabilization by peak current regulation in reactive high-power impulse magnetron sputtering of hafnium nitride. Journal Physics D: Applied Physics, 2016, 49, 065202.	1.3	22

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37	Highly reflective rear surface passivation design for ultra-thin Cu(In,Ga)Se 2 solar cells. Thin Solid Films, 2015, 582, 300-303.	0.8	51
38	Publisher's Note: Molecular dynamics simulation of the growth of Cu nanoclusters from Cu ions in a plasma [Phys. Rev. B90, 165421 (2014)]. Physical Review B, 2015, 91, .	1.1	0
39	Synthesis of titanium-oxide nanoparticles with size and stoichiometry control. Journal of Nanoparticle Research, 2015, 17, 1.	0.8	21
40	The use of Highly Ionized Pulsed Plasmas for the Synthesis of Advanced Thin Films and Nanoparticles. KONA Powder and Particle Journal, 2014, 31, 171-180.	0.9	7
41	Characterisation of Nanoparticle Structure by High Resolution Electron Microscopy. Journal of Physics: Conference Series, 2014, 522, 012065.	0.3	1
42	Double oxide shell layer formed on a metal nanoparticle as revealed by aberration corrected (scanning) transmission electron microscopy. Materials Research Express, 2014, 1, 025016.	0.8	6
43	Principles for designing sputtering-based strategies for high-rate synthesis of dense and hard hydrogenated amorphous carbon thin films. Diamond and Related Materials, 2014, 44, 117-122.	1.8	16
44	Deposition of yttria-stabilized zirconia thin films by high power impulse magnetron sputtering and pulsed magnetron sputtering. Surface and Coatings Technology, 2014, 240, 1-6.	2.2	24
45	Molecular dynamics simulation of the growth of Cu nanoclusters from Cu ions in a plasma. Physical Review B, 2014, 90, .	1.1	5
46	Understanding the discharge current behavior in reactive high power impulse magnetron sputtering of oxides. Journal of Applied Physics, 2013, 113, .	1.1	86
47	Size-controlled growth of nanoparticles in a highly ionized pulsed plasma. Applied Physics Letters, 2013, 102, .	1.5	42
48	Modeling the extraction of sputtered metal from high power impulse hollow cathode discharges. Plasma Sources Science and Technology, 2013, 22, 035006.	1.3	17
49	Fast growth of nanoparticles in a hollow cathode plasma through orbit motion limited ion collection. Applied Physics Letters, 2013, 103, 193108.	1.5	33
50	Time-domain and energetic bombardment effects on the nucleation and coalescence of thin metal films on amorphous substrates. Journal Physics D: Applied Physics, 2013, 46, 215303.	1.3	19
51	High power impulse magnetron sputtering discharge. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2012, 30, .	0.9	568
52	Growth of Ti-C nanocomposite films by reactive high power impulse magnetron sputtering under industrial conditions. Surface and Coatings Technology, 2012, 206, 2396-2402.	2.2	58
53	ZrB2 thin films grown by high power impulse magnetron sputtering from a compound target. Thin Solid Films, 2012, 526, 163-167.	0.8	58
54	Influence of ionization degree on film properties when using high power impulse magnetron sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2012, 30, .	0.9	28

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55	A strategy for increased carbon ionization in magnetron sputtering discharges. Diamond and Related Materials, 2012, 23, 1-4.	1.8	97
56	Understanding deposition rate loss in high power impulse magnetron sputtering: I. Ionization-driven electric fields. Plasma Sources Science and Technology, 2012, 21, 025005.	1.3	64
57	Internal current measurements in high power impulse magnetron sputtering. Plasma Sources Science and Technology, 2011, 20, 045003.	1.3	35
58	Studies of hysteresis effect in reactive HiPIMS deposition of oxides. Surface and Coatings Technology, 2011, 205, S303-S306.	2.2	59
59	Hysteresis and process stability in reactive high power impulse magnetron sputtering of metal oxides. Thin Solid Films, 2011, 519, 7779-7784.	0.8	82
60	Two-domain formation during the epitaxial growth of GaN (0001) on <i>c</i>-plane Al2O3 (0001) by high power impulse magnetron sputtering. Journal of Applied Physics, 2011, 110, .	1.1	18
61	Effect of peak power in reactive high power impulse magnetron sputtering of titanium dioxide. Surface and Coatings Technology, 2011, 205, 4828-4831.	2.2	70
62	On the film density using high power impulse magnetron sputtering. Surface and Coatings Technology, 2010, 205, 591-596.	2.2	317
63	Lowâ€Temperature Superionic Conductivity in Strained Yttriaâ€Stabilized Zirconia. Advanced Functional Materials, 2010, 20, 2071-2076.	7.8	150
64	Fully dense, non-faceted 111-textured high power impulse magnetron sputtering TiN films grown in the absence of substrate heating and bias. Thin Solid Films, 2010, 518, 5978-5980.	0.8	101
65	Dual-magnetron open field sputtering system for sideways deposition of thin films. Surface and Coatings Technology, 2010, 204, 2165-2169.	2.2	27
66	Ab initio calculations and synthesis of the off-stoichiometric half-Heusler phase Ni1â^'xMn1+xSb. Journal of Applied Physics, 2010, 108, 093712.	1.1	10
67	Faster-than-Bohm Cross-<mml:math xmlns:mml="http://www.w3.org/1998/Math/MathML" display="inline"><mml:mi>B</mml:mi></mml:math>Electron Transport in Strongly Pulsed Plasmas. Physical Review Letters, 2009, 103, 225003.	2.9	49
68	Low-temperature Î±-alumina thin film growth:ab initiostudies of Al adatom surface migration. Journal Physics D: Applied Physics, 2009, 42, 125302.	1.3	11
69	Î±-Alumina coatings on WC/Co substrates by physical vapor deposition. International Journal of Refractory Metals and Hard Materials, 2009, 27, 507-512.	1.7	37
70	On the electron energy in the high power impulse magnetron sputtering discharge. Journal of Applied Physics, 2009, 105, .	1.1	76
71	Transition between the discharge regimes of high power impulse magnetron sputtering and conventional direct current magnetron sputtering. Plasma Sources Science and Technology, 2009, 18, 045008.	1.3	79
72	Energy flux measurements in high power impulse magnetron sputtering. Journal Physics D: Applied Physics, 2009, 42, 185202.	1.3	60

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73	The spatial and temporal variation of the electron energy distribution function (EEDF) in the HiPIMS discharge. , 2009, , .		0
74	Hysteresis-free reactive high power impulse magnetron sputtering. Thin Solid Films, 2008, 516, 6398-6401.	0.8	123
75	Influence of residual water on magnetron sputter deposited crystalline Al2O3 thin films. Thin Solid Films, 2008, 516, 3877-3883.	0.8	28
76	Anomalous electron transport in high power impulse magnetron sputtering. Plasma Sources Science and Technology, 2008, 17, 025007.	1.3	58
77	Synthesis of Î±-Al ₂ O ₃ thin films using reactive high-power impulse magnetron sputtering. Europhysics Letters, 2008, 82, 36002.	0.7	82
78	Cross-field ion transport during high power impulse magnetron sputtering. Plasma Sources Science and Technology, 2008, 17, 035021.	1.3	106
79	A bulk plasma model for dc and HiPIMS magnetrons. Plasma Sources Science and Technology, 2008, 17, 045009.	1.3	48
80	Phase tailoring of Ta thin films by highly ionized pulsed magnetron sputtering. Thin Solid Films, 2007, 515, 3434-3438.	0.8	104
81	Ab initiostudies of Al, O, andO2adsorption onÎ±âˆ’Al2O3(0001)surfaces. Physical Review B, 2006, 74, .	1.1	42
82	Investigation of RuO2/4Hâ€“SiC Schottky diode contacts by deep level transient spectroscopy. Chemical Physics Letters, 2006, 429, 617-621.	1.2	11
83	Investigation of high power impulse magnetron sputtering pretreated interfaces for adhesion enhancement of hard coatings on steel. Surface and Coatings Technology, 2006, 200, 6495-6499.	2.2	131
84	Phase control of Al2O3 thin films grown at low temperatures. Thin Solid Films, 2006, 513, 57-59.	0.8	91
85	Ionized physical vapor deposition (IPVD): A review of technology and applications. Thin Solid Films, 2006, 513, 1-24.	0.8	886
86	The ion energy distributions and ion flux composition from a high power impulse magnetron sputtering discharge. Thin Solid Films, 2006, 515, 1522-1526.	0.8	279
87	High-power impulse magnetron sputtering of Tiâ€“Siâ€“C thin films from a Ti3SiC2 compound target. Thin Solid Films, 2006, 515, 1731-1736.	0.8	96
88	Guiding the deposition flux in an ionized magnetron discharge. Thin Solid Films, 2006, 515, 1928-1931.	0.8	88
89	Molecular content of the deposition flux during reactive Arâˆ•O2 magnetron sputtering of Al. Applied Physics Letters, 2006, 88, 054101.	1.5	10
90	Energy distributions of positive and negative ions during magnetron sputtering of an Al target in Arâˆ•O2 mixtures. Journal of Applied Physics, 2006, 100, 033305.	1.1	53

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91	Radio frequency dual magnetron sputtering deposition and characterization of nanocomposite Al2O3â€“ZrO2 thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2006, 24, 309-316.	0.9	27
92	Deep energy levels in RuO2âˆ•4Hâ€“SiC Schottky barrier structures. Applied Physics Letters, 2006, 88, 153509.	1.5	12
93	Hydrogen sensing by NKN thin film with high dielectric constant and ferroelectric property. Sensors and Actuators B: Chemical, 2005, 108, 490-495.	4.0	3
94	Solâ€“gel synthesis and characterization of Na0.5K0.5NbO3 thin films. Journal of Crystal Growth, 2005, 281, 468-474.	0.7	54
95	Erratum to â€œSpatial Electron Density Distribution in a High-Power Pulsed Magnetron Dischargeâ€• IEEE Transactions on Plasma Science, 2005, 33, 1129-1129.	0.6	1
96	Spatial electron density distribution in a high-power pulsed magnetron discharge. IEEE Transactions on Plasma Science, 2005, 33, 346-347.	0.6	100
97	Ionization of sputtered metals in high power pulsed magnetron sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2005, 23, 18-22.	0.9	214
98	Eliminating the hysteresis effect for reactive sputtering processes. Applied Physics Letters, 2005, 86, 164106.	1.5	43
99	Plasma dynamics in a highly ionized pulsed magnetron discharge. Plasma Sources Science and Technology, 2005, 14, 525-531.	1.3	98
100	Ab initiocalculations on the effects of additives on alumina phase stability. Physical Review B, 2005, 71, .	1.1	25
101	Ion-assisted physical vapor deposition for enhanced film properties on nonflat surfaces. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2005, 23, 278-280.	0.9	211
102	Ion-acoustic solitary waves in a high power pulsed magnetron sputtering discharge. Journal Physics D: Applied Physics, 2005, 38, 3417-3421.	1.3	36
103	Effect of chemical composition on the elastic and electrical properties of the boron-oxygen-yttrium system studied byab initioand experimental means. Physical Review B, 2004, 69, .	1.1	1
104	Microstructure of Î±-alumina thin films deposited at low temperatures on chromia template layers. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 117-121.	0.9	99
105	Measurement of the magnetic field change in a pulsed high current magnetron discharge. Plasma Sources Science and Technology, 2004, 13, 654-661.	1.3	64
106	Properties of Alâ€“SrTiO<tex>$_3$</tex>â€“ITO Capacitors for Microelectronic Device Applications. IEEE Transactions on Electron Devices, 2004, 51, 1202-1205.	1.6	6
107	Effects of additives in Î±- and Î¸-alumina: an ab initio study. Journal of Physics Condensed Matter, 2004, 16, 8971-8980.	0.7	32
108	Comparison of microstructure and mechanical properties of chromium nitride-based coatings deposited by high power impulse magnetron sputtering and by the combined steered cathodic arc/unbalanced magnetron technique. Thin Solid Films, 2004, 457, 270-277.	0.8	196

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109	Microstructure/dielectric property relationship of low temperature synthesised (Na,K)NbOx thin films. Journal of Crystal Growth, 2004, 262, 322-326.	0.7	16
110	Elastic modulus-density relationship for amorphous boron suboxide thin films. Applied Physics A: Materials Science and Processing, 2003, 76, 269-271.	1.1	30
111	Low temperature growth and characterization of (Na,K)NbOx thin films. Journal of Crystal Growth, 2003, 254, 400-404.	0.7	18
112	High power pulsed magnetron sputtered CrN films. Surface and Coatings Technology, 2003, 163-164, 267-272.	2.2	242
113	Quantum design and synthesis of a boronâ€“oxygenâ€“yttrium phase. Applied Physics Letters, 2003, 82, 4286-4288.	1.5	1
114	Role of carbon in boron suboxide thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2003, 21, 1355-1358.	0.9	10
115	Elastic modulus of amorphous boron suboxide thin films studied by theoretical and experimental methods. Journal of Applied Physics, 2003, 93, 940-944.	1.1	18
116	Stabilization of potential superhardRuO2phases: A theoretical study. Physical Review B, 2002, 66, .	1.1	17
117	Low temperature deposition of Î±-Al[sub 2]O[sub 3] thin films by sputtering using a Cr[sub 2]O[sub 3] template. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2002, 20, 2134.	0.9	103
118	Synthesis and mechanical properties of boron suboxide thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2002, 20, 335-337.	0.9	24
119	Growth and Characterization of Na_{0.5}K_{0.5}NbO₃ Thin Films on Polycrystalline Pt₈₀Ir₂₀ Substrates. Journal of Materials Research, 2002, 17, 1183-1191.	1.2	24
120	Characteristics of SrTiO₃ thin films deposited on Si by rf magnetron sputtering at various substrate temperatures. The Philosophical Magazine: Physics of Condensed Matter B, Statistical Mechanics, Electronic, Optical and Magnetic Properties, 2002, 82, 891-903.	0.6	6
121	Electrical characterisation of SrTiO3/Si interfaces. Journal of Non-Crystalline Solids, 2002, 303, 185-189.	1.5	14
122	Influence of high-energy Si+ ion irradiation on microstructure and mechanical properties of alumina films. Surface and Coatings Technology, 2002, 158-159, 534-537.	2.2	12
123	Spatial and temporal behavior of the plasma parameters in a pulsed magnetron discharge. Surface and Coatings Technology, 2002, 161, 249-256.	2.2	189
124	Optical properties of anatase TiO2 thin films prepared by aqueous solâ€“gel process at low temperature. Thin Solid Films, 2002, 405, 50-54.	0.8	286
125	Influence of high power densities on the composition of pulsed magnetron plasmas. Vacuum, 2002, 65, 147-154.	1.6	268
126	Characteristics of SrTiO 3 thin films deposited on Si by rf magnetron sputtering at various substrate temperatures. The Philosophical Magazine: Physics of Condensed Matter B, Statistical Mechanics, Electronic, Optical and Magnetic Properties, 2002, 82, 891-903.	0.6	6

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127	High Li+-Ion Storage Capacity and Double-Electrochromic Behavior of Solâˆ’Gel-Derived Iron Oxide Thin Films with Sulfate Residues. Chemistry of Materials, 2001, 13, 1976-1983.	3.2	24
128	Electrical properties of SrTiO3 thin films on Si deposited by magnetron sputtering at low temperature. Applied Physics Letters, 2001, 79, 1513-1515.	1.5	53
129	Evolution of the electron energy distribution and plasma parameters in a pulsed magnetron discharge. Applied Physics Letters, 2001, 78, 3427-3429.	1.5	141
130	Microwave properties of tunable capacitors basee on magnetron sputtered ferroelectric Na0.5K0.5NbO3 film on low and high resistivity silicon substrates. Integrated Ferroelectrics, 2001, 39, 359-366.	0.3	4
131	RF-Magnetron Sputtered Au/(Na,K)NbO3/SiO2/Si MFIS-diode Structures. Materials Research Society Symposia Proceedings, 2001, 688, 1.	0.1	2
132	Pt/CeO2 SIC Schottky diodes with high response to hydrogen and hydrocarbons. , 2001, , 832-835.		9
133	Growth of SrTiO3 thin films on LaAlO3(001) substrates; the influence of growth temperature on composition, orientation, and surface morphology. Thin Solid Films, 2000, 360, 181-186.	0.8	10
134	Epitaxial growth of W-doped VO2/V2O3 multilayer on Î±-Al2O3(110) by reactive magnetron sputtering. Thin Solid Films, 2000, 375, 128-131.	0.8	34
135	Electrostatic powder impact deposition (EPID) of Ge on Si and Cu substrates, microstructure and morphology study. Journal Physics D: Applied Physics, 2000, 33, 1155-1160.	1.3	0
136	Ionized sputter deposition using an extremely high plasma density pulsed magnetron discharge. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2000, 18, 1533-1537.	0.9	235
137	Peroxo solâ€“gel preparation: photochromic/electrochromic properties of Moâ€“Ti oxide gels and thin films. Journal of Materials Chemistry, 2000, 10, 2396-2400.	6.7	24
138	Evaluation of Intermittent Contact Mode AFM Probes by HREM and Using Atomically Sharp CeO2Ridges as Tip Characterizer. Langmuir, 2000, 16, 6267-6277.	1.6	34
139	Composition, structure, and dielectric tunability of epitaxial SrTiO3 thin films grown by radio frequency magnetron sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1999, 17, 564-570.	0.9	41
140	Growth and characterization of epitaxial films of tungsten-doped vanadium oxides on sapphire (110) by reactive magnetron sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1999, 17, 1817-1821.	0.9	25
141	Reduction of density of subgrain boundaries and misfit dislocations in epitaxial (001) SrTiO3 thin films: Effect on dielectric tunability. Journal of Applied Physics, 1999, 85, 3976-3983.	1.1	12
142	Epitaxial cerium oxide buffer layers and YBa₂Cu₃O_{7âˆ’Î´} thin films for microwave device applications. Journal of Materials Research, 1999, 14, 2385-2393.	1.2	28
143	Morphology changes of thin Pd films grown on SiO 2 : influence of adsorbates and temperature. Thin Solid Films, 1999, 342, 297-306.	0.8	19
144	A novel pulsed magnetron sputter technique utilizing very high target power densities. Surface and Coatings Technology, 1999, 122, 290-293.	2.2	910

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145	Monte Carlo simulations of the transport of sputtered particles. Computer Physics Communications, 1999, 120, 238-254.	3.0	18
146	Carbon Monoxide Oxidation on Copper Oxide Thin Films Supported on Corrugated Cerium Dioxide {111} and {001} Surfaces. Journal of Catalysis, 1999, 181, 6-15.	3.1	41
147	Title is missing!. Journal of Materials Science: Materials in Electronics, 1999, 10, 203-208.	1.1	4
148	Hydrogen uptake in alumina thin films synthesized from an aluminum plasma stream in an oxygen ambient. Applied Physics Letters, 1999, 74, 200-202.	1.5	73
149	Low temperature growth of SrTiO3thin films on glass fiber laminate substrates. Ferroelectrics, 1999, 225, 287-294.	0.3	1
150	Sharp microfaceting of (001)-oriented cerium dioxide thin films and the effect of annealing on surface morphology. Surface Science, 1999, 429, 22-33.	0.8	68
151	Determination of the complex dielectric function of epitaxial SrTiO3 films using transmission electron energy-loss spectroscopy. Journal of Applied Physics, 1999, 85, 2828-2834.	1.1	27
152	Dislocations, strain, and defects in heteroepitaxial YBa2Cu3O7â^'x/SrTiO3 multilayers. Physica C: Superconductivity and Its Applications, 1998, 304, 307-313.	0.6	9
153	Formation of secondary phases in YBa2Cu3O7â^'Î'/SrTiO3 multilayers. Physica C: Superconductivity and Its Applications, 1998, 304, 245-254.	0.6	10
154	Modeling of the deposition of stoichiometric Al2O3 using nonarcing direct current magnetron sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1998, 16, 1286-1292.	0.9	10
155	Growth and field dependent dielectric properties of epitaxial Na0.5K0.5NbO3 thin films. Applied Physics Letters, 1998, 73, 927-929.	1.5	90
156	High rate reactive dc magnetron sputter deposition of Al2O3 films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1998, 16, 639-643.	0.9	42
157	Microstructure and microwave dielectric properties of epitaxial SrTiO3 films on LaAlO3 substrates. Journal of Applied Physics, 1998, 83, 4884-4890.	1.1	28
158	Plasma characteristics at off-axis high pressure magnetron YBa2Cu3O7â^'Î´ sputtering. Journal of Applied Physics, 1997, 82, 1882-1889.	1.1	36
159	HTS/ferroelectric devices for microwave applications. IEEE Transactions on Applied Superconductivity, 1997, 7, 2458-2461.	1.1	46
160	High resolution X-ray diffraction mapping studies on the domain structure of LaAlO3 single crystal substrates and its influence on SrTiO3 film growth. Journal of Crystal Growth, 1997, 171, 401-408.	0.7	24
161	Modelling of thin-film HTS/ferroelectric interdigital capacitors. IET Microwaves Antennas and Propagation, 1996, 143, 397.	1.2	44
162	Structural and electrical characterization of sputter-deposited SrTiO3 thin films. Microelectronic Engineering, 1995, 29, 123-127.	1.1	13

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163	Microstructure of SrTiO₃ Thin Films as Single Layer and Incorporated in Yba₂Cu₃O_{7-x}/SrTiO₃ Multilayers. Materials Research Society Symposia Proceedings, 1995, 401, 369.	0.1	2
164	Magnetoconductivity inYBa2Cu3O7âˆ’Î´thin films. Physical Review B, 1995, 52, 3748-3755.	1.1	28
165	A spectroscopic ellipsometry study of cerium dioxide thin films grown on sapphire by rf magnetron sputtering. Journal of Applied Physics, 1995, 77, 5369-5376.	1.1	186
166	Reduction of surface particles on YBa2Cu3O7âˆ’âˆ‚thin films through the use of nonstoichiometric sputtering targets and N2O in the sputtering gas. Journal of Applied Physics, 1995, 77, 6388-6393.	1.1	18
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